

# Finite Element Modeling and Simulation of A Microstructure Silicon Beam Resonant

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## Abstract

The silicon sensor is more than 25 years old, though the term ‘silicon sensors’ had not yet been coined when the first devices were conceived. The very first silicon sensors used silicon diodes for the detection of light. These photodiodes were normal diodes which had the lacquer on their transparent packages scratched off. Around the same time it became known that temperature could be measured by analyzing the temperature sensitivity of the forward current of a simple diode. This paper establishes the Finite Element Method (FEM) model of a practical silicon beam resonator attached to a diaphragm used for measuring pressure. In this paper presents two location error models. Analyze, calculate, and investigate the relationship between the basic natural frequency of the beam resonator and the measured pressure for two error models are discussed.

**Keywords:** Finite Element Method, Beam Resonant, Pressure

## 1. Introduction

During the past decade, many experts in sensor technology have noticed the rapid development in silicon resonant sensors. The silicon microstructure resonant sensors are noted for the advantages of a generalized resonant sensor, such as direct digital output (without A/D conversion), long-term stability, low hysteresis and high repeatability. Other advantages of silicon material are excellent mechanical properties; high strength; free from mechanical hysteresis; suit ability to batch processing at low cost; and the compatibility of mechanical and electrical properties. Meanwhile, the dynamic characteristics of silicon resonant sensors are much better than those of conventional ones, due to their high working frequency [1]. In addition, the temperature characteristics of silicon resonant sensors are much better than those of another important silicon sensor, the piezo resistive sensor. It is much easier to interface them with a microprocessor to develop smart or ‘intelligent’ sensors or sensor systems due to their unique operating principle based on the relationship between the natural frequency and measured signal instead of the silicon piezo resistive effect. Recently, it has been reported that some prototypes, with different structure and configurations, and even few batch products of silicon resonant sensors have come into being for measuring pressure, differential pressure or force.

They have been developed and manufactured in Japan, USA, Netherlands and Britain. Although the properties of these silicon resonant sensors have not reached the designed criteria, they could be used widely in many technical fields in the near future.

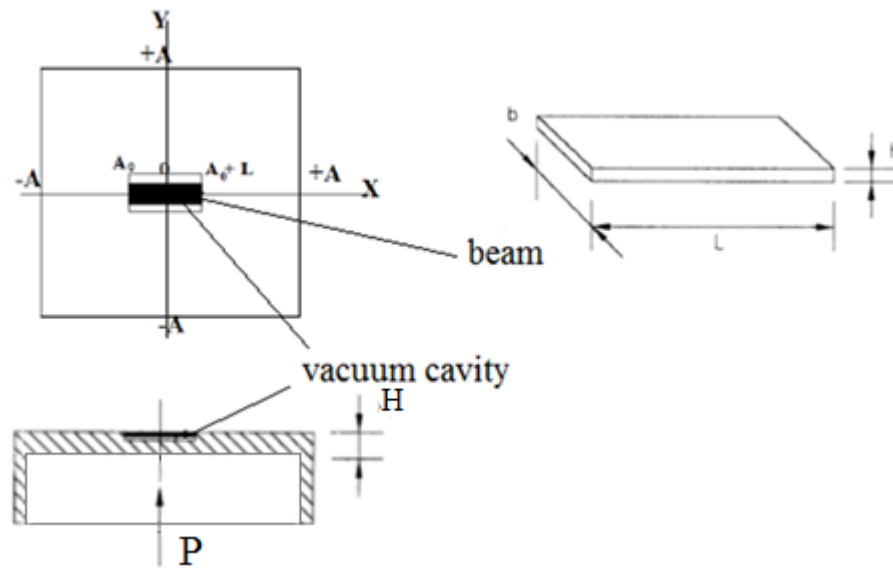


Figure 1. Sensing structure of the sensor.

Figure 1 shows the structure of a silicon resonant sensor for measuring pressure. The preliminary sensing unit is a square diaphragm. The measured pressure acts perpendicularly to the lower surface of the diaphragm and yields the stress. The final sensing unit is a beam, which is attached to the upper surface of the diaphragm. Moreover, the thickness of the beam  $h$  should be much less than the thickness of the diaphragm  $H$ , and the width of the beam should be less than the half length of the diaphragm  $A$ . Based on the above structural feature, an appropriate initial stress is applied along the axial direction of the beam, which is almost identical with the stress of the square diaphragm at the same position. Thus the natural frequency of the beam is varied with the applied pressure which acts on the square diaphragm. Therefore, the pressure will be measured via the change in natural frequency of the beam. In addition, the beam resonator has a very high  $Q$  factor because it can be packaged within a vacuum housing.

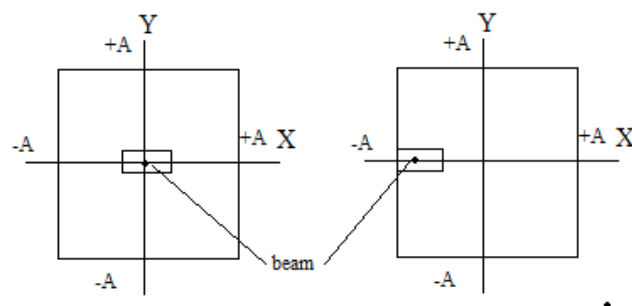


Figure 2. Ideal locations of the beam at the diaphragm.

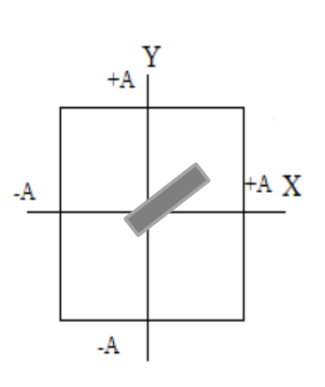


Figure 3. Error model 1 of beam's location at the diaphragm

Figure 2 shows the ideal location scheme of the beam. Figure 3 shows the location error model 1 within the positive stress range, while Figure 4 shows the location error model 2 within the negative stress range. It is certain that the frequency-pressure relationship varies with the deviation B in the x-axis, deviation D in the y-axis and the angular deviation a relative to its ideal location for the above error cases. In order to improve the exchangeability of the sensor, it is necessary to investigate the influence laws of the above deviations on the frequency-pressure relationship of the beam resonator. The objective of this paper is to study the above problems in order to obtain some directions during developing the silicon resonator sensors by making use of a finite element model (FEM).

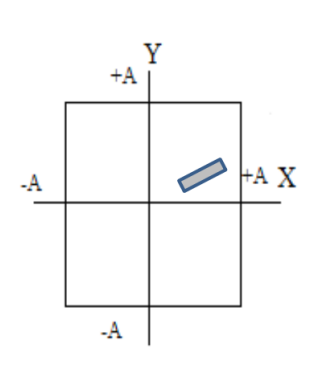


Figure 4. Error model 2 of beam's location at the diaphragm

**Stresses on the upper surface of the square diaphragm**

According to the structural feature and the design demands for the sensor, the square diaphragm is within the range of a small deflection. Then the differential equation can be written as follows:

$$\frac{\partial^4 W(x, y)}{\partial x^4} + 2 \frac{\partial^4 W(x, y)}{\partial x^2 \partial y^2} + \frac{\partial^4 W(x, y)}{\partial y^4} = \frac{P}{D_s} \tag{1}$$

Where 
$$D_s = \frac{EH^3}{12(1-\mu^2)}$$

Where  $W(x,y)$  Displacement of the square diaphragm under the applied pressure P, and  $D_s$  The flexural rigidity of the square diaphragm.

According to the built-in edge of the square diaphragm, its displacement can be assumed as follows:

$$W(x, y) = W_{\max} H \left( \frac{x^2}{A^2} - 1 \right)^2 \left( \frac{y^2}{A^2} - 1 \right)^2 \tag{2}$$

Where  $W_{\max}$  Ratio between the maximum normal displacement and the thickness of the square diaphragm, and  $A, H$  Half-length and thickness of the square diaphragm.

Substituting Eq. (2) into Eq. (1), the displacement  $W(x,y)$  can be obtained. Then stresses on the upper surface of the square diaphragm can be obtained.

$$\begin{aligned} \rho_x(x, y) &= -\frac{49p}{96} \left( \frac{A}{H} \right)^2 \left[ \left( \frac{3x^2}{A^2} - 1 \right) \left( \frac{y^2}{A^2} - 1 \right)^2 + \mu \left( \frac{x^2}{A^2} - 1 \right)^2 \left( \frac{3y^2}{A^2} - 1 \right) \right] \\ \rho_y(x, y) &= -\frac{49p}{96} \left( \frac{A}{H} \right)^2 \left[ \left( \frac{3y^2}{A^2} - 1 \right) \left( \frac{x^2}{A^2} - 1 \right)^2 + \mu \left( \frac{y^2}{A^2} - 1 \right)^2 \left( \frac{3x^2}{A^2} - 1 \right) \right] \end{aligned} \tag{3}$$

Where  $\sigma_x(x,y), \sigma_y(x,y)$  Stresses of the square diaphragm.

**Finite element model of the beam**

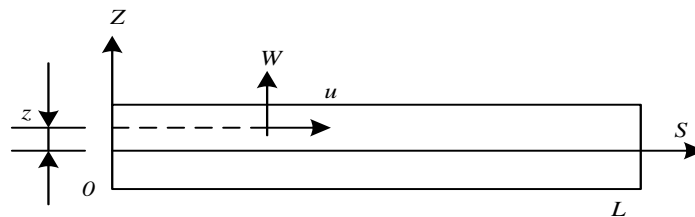


Figure 5. Mathematical model of the beam

Figure 5 shows the mathematical model of the beam. The vibrating displacements of the beam at an arbitrary point are as follows:

$$\begin{cases} u(s, z, t) = -z \frac{dw(s)}{ds} \cos \omega t \\ w(s, t) = w(s) \cos \omega t \end{cases} \tag{4}$$

Where  $u(s, z, t)-w(s, t)$  Axial and normal vibrating displacements of the beam in Cartesian coordinate of the beam, and  $s, z$  Axial and normal coordinates of the beam in Cartesian coordinate of the beam.

Energy expressions of the beam resonator are as follows

The potential energy

$$U = \frac{Ebh^3 \cos^2 \omega t}{24} \int_s \left[ \frac{d^2 w(s)}{ds^2} \right]^2 ds \tag{5}$$

Where  $U$  Potential energy of the beam ,and  $S$  is the integrated length of the beam.

The kinetic energy

$$T = \frac{\rho b h \omega^2 \sin^2 \omega t}{2} \int_s [w(s)]^2 ds \quad (6)$$

Where  $T$  Kinetic energy of the beam, and  $\rho$  density of the sensing structure.

In addition, the initial potential energy of the beam, which is caused by  $\sigma_s^0(s)$ , is

$$U_0 = -\frac{bh \cos^2 \omega t}{2} \int_s \sigma_s^0(s) \left[ \frac{dw(s)}{ds} \right]^2 ds \quad (7)$$

From Fig(1) and equation (3), according to the above analyses,

$$\sigma_s^0(s) = \sigma_x(x,0) = \frac{49P}{96} \left( \frac{A}{H} \right)^2 \left[ \left( \frac{3x^2}{A^2} - 1 \right) - \mu \left( \frac{x^2}{A^2} - 1 \right)^2 \right] \quad (8)$$

Where  $\sigma_s^0(s)$  Initial axial stress of the beam.

The following relation for the error cases:

$$\sigma_s^0(s) = \sin^2 \beta(s) \sigma_x(x, y) + \cos^2 \beta(s) \sigma_y(x, y) \quad (9)$$

Then the total potential energy of the beam is

$$U_T = U - U_0 \quad (10)$$

Where  $U_0$  Initial potential energy of the beam, which is caused by  $\sigma_s^0(s)$ , and  $U_T$  Total potential energy of the beam.

In Eq. (7), if  $\omega$  is a constant aft, the analytic relationship between the basic natural frequency and the initial axial stress can be directly obtained:

$$\omega = \frac{22.38h}{L^2} \sqrt{\frac{E}{12\sigma}} \sqrt{1 + 0.295 \frac{\sigma_s^0 L^2}{Eh^2}} \quad (11)$$

Where  $\omega$ [rad/s],  $w(s)$  Natural frequency and its corresponding vibrating shape along the axial direction of the beam.

However, from Eqs. (3), (8) and (9),  $\sigma_s^0(s)$  is varying. Therefore, The the finite element equation of the beam resonator can be written as follows:

$$\left( \mathbf{K} - \omega^2 \mathbf{M} \right) \mathbf{a} = 0 \quad (12)$$

where  $\mathbf{K}$ -assembly stiffness Matrix,  $\mathbf{M}$ -assembly Mass Matrix,  $\mathbf{a}$  the assembly nodal vector, consisting of all  $a_j$ .

For the actual structural features of Fig. 1, the boundary conditions of the beam are as follows

$$\begin{cases} s = -a: & w(s) = w^\circ(s) = 0 \\ s = +a: & w(s) = w^\circ(s) = 0 \end{cases} \quad (13)$$

From Eqs. (12), (13), natural frequencies and the corresponding vibrating shapes of the beam resonator can be obtained.

## 2. Calculations and Simulations

In this work, the main investigate the detailed vibration shape of the beam resonator simultaneously. The sensor is made of silicon,  $E = 1.3 \times 10^{11}$  Pa,  $\rho = 2.33 \times 10^3$  kg/m<sup>3</sup>,  $\mu = 0.17$ . Moreover, the total element number of the beam N is 19 for FEM calculation. The half-length and thickness of the square diaphragm are  $A=1$ mm and  $H=0.1$  mm, respectively. In addition, the width and thickness of the beam are  $b=50$   $\mu$ m and  $h=5$  $\mu$ m.

Define,  $\Delta f(B, D, a)$  [hz] =  $\Delta f(P, B, D, a) - f(0, 0, 0, 0)$  as the variation of the basic natural frequency of the beam within (0, p), with the x-axis deviation B. y-axis deviation D and the angular deviation a relative to its ideal location.

Define  $\beta(B, D, a) = [\Delta f(B, D, a) - \Delta f(0, 0, 0)] / \Delta f(0, 0, 0)$  as the relative variation of the basic natural frequency variation of the beam within (0, P), with the x-axis deviation B. y-axis deviation D and the angular deviation a relative to its ideal location.

Table 1. The relative variation  $\beta(B, D, 0)$  of the frequency variation of the beam.

D $\mu$ m	B $\mu$ m			
	0	2	4	6
0	0.001	0.001	0.001	0.001
2	0.002	0.001	0.001	0.001
4	0	0.001	0.001	0.001
6	0.001	0.001	0.001	0.001

Table 2. The relative variation  $\beta(B, D, 3)$  of the frequency variation of the beam.

D $\mu$ m	B $\mu$ m			
	0	2	4	6
0	0.002	0.002	0.001	0.001
2	0.001	0.001	0.002	0.002
4	0.001	0.001	0.001	0
6	0.001	0.001	0.001	0.001

**Table 3.** The relative variation  $\beta(B, D, -3)$  of the frequency variation of the beam.

$D \mu m$	$B \mu m$			
	0	2	4	6
0	0.001	0.002	0.001	0.001
2	0	0.002	0.001	0.001
4	0.001	0.002	0	0.001
6	0.002	0.001	0.002	0.001

Table's 1~3 shows  $\beta(B, D, 0)$ , ( $a=0\text{deg}$ ),  $\beta(B, D, 3)$  ( $a=+3\text{deg}$ ) and  $\beta(B, D, -3)$  ( $a=-3\text{deg}$ ), within  $(0, 10^6)\text{pa}$ . as the beam is located at different positions, i. e., with different  $x$ -axis deviation  $B$ ,  $y$ -axis deviation  $D$  and the angular deviation  $a$  relative to its ideal location on the square diaphragm. The design ideal location is  $(-300, +300) \mu m$  (or  $L=600\mu m$ ) within the positive stress range of the beam, and the beam's axial direction is along the  $x$ - axis of the square diaphragm, which corresponds to  $B = 0, D=0, a=0$ . In addition,  $f(0, 0, 0)=106648\text{Hz}$ .  $\Delta f(0, 0, 0)=9924\text{Hz}$ .

From Table's 1~3, the variation of the basic natural frequency of the beam, which is influenced by the deviation  $D$ , the deviation  $B$ , and the angular deviation  $a$  of the beam relative to its ideal location, are almost the same within the positive stress range.

Table's 4~6 shows  $\beta(B, D, 0)$ , ( $a=0\text{deg}$ ),  $\beta(B, D, 3)$  ( $a=+3\text{deg}$ ) and  $\beta(B, D, -3)$  ( $a=3\text{deg}$ ), within  $(0, 10^6)\text{pa}$ . as the beam is located at different positions, i. e., with different  $x$ -axis deviation  $B$ ,  $y$ -axis deviation  $D$  and the angular deviation  $a$  relative to its ideal location on the square diaphragm. The design ideal location is  $(+700, +1000) \mu m$  (or  $L=200\mu m$ ) within the negative stress range of the beam, and the beam's axial direction is along the  $x$ - axis of the square diaphragm, which corresponds to  $B = 0, D=0, a=0$ . In addition,  $f(0, 0, 0)=426564\text{Hz}$ .  $\Delta f(0, 0, 0)=10475\text{Hz}$ .

**Table 4.** The relative variation  $\beta(B, D, 0)$  of the frequency variation of the beam.

$D \mu m$	$B \mu m$			
	0	-2	-4	-6
0	0	-0.005	-0.019	-0.025
2	0	-0.006	-0.021	-0.025
4	0.001	-0.006	-0.018	-0.026
6	0.002	-0.005	-0.018	-0.025

**Table 5.** The relative variation  $\beta(B, D, 3)$  of the frequency variation of the beam.

$D \mu m$	$B \mu m$			
	0	-2	-4	-6
0	-0.001	-0.008	-0.021	-0.026
2	-0.001	-0.011	-0.021	-0.026
4	-0.001	-0.012	-0.017	-0.031
6	-0.002	-0.013	-0.023	-0.029

Table 6. The relative variation  $\beta(B, D, -3)$  of the frequency variation of the beam.

D $\mu\text{m}$	B $\mu\text{m}$			
	0	-2	-4	-6
0	-0.001	-0.008	-0.025	-0.030
2	-0.001	-0.012	-0.025	-0.030
4	-0.001	-0.012	-0.026	-0.030
6	-0.002	-0.010	-0.025	-0.033

From Table's 1~3, the variation of the basic natural frequency of the beam, which is influenced by the deviation  $D$ , the deviation  $B$ , and the angular deviation  $\alpha$  of the beam relative to its ideal location, within the negative stress range. Therefore, the y-axis deviation B should be reduced as much as possible. Comparing the above tables, it is obvious that locating the beam in the middle of the square diaphragm is much better than at the edge.

## 4. Conclusions

Based on the Finite Element Method model and analyses of the initial stresses applied to the beam resonator attached to a square diaphragm, this paper first calculates, analyzes and investigates the relationship between the basic natural frequency of the beam resonator and the measured pressure for two error models. An important result is obtained it is necessary to monitor the processing accuracy in the x-axis, y-axis and the reference angle  $\alpha$  relative to the ideal coordinate, within the positive stress range, while only in the x-axis within the negative stress range as the beam axial direction is along the x-axis of the square diaphragm. In addition, locating the beam in the middle of the square diaphragm is much better than at the edge.

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